

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	2394	((((356/237.1 or 356/237.2) or 356/237.3) or 356/237.4) or 356/237.5) or 356/237.6)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/06 11:44
L2	1150	356/237.1	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/06 11:45
L3	64	1 and in near situ	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/06 11:45
L4	46	3 and particles	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/06 11:56
L5	0	film near2 peel\$3 and 4	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/06 11:46
L6	0	film near2 peel\$3 and 3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/06 11:46
L7	9	film near2 peel\$3 and 1	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/06 11:46
L8	19	situ near2 method and ((detect\$3 or measur\$3) or monitor\$3) near15 ((particle or defect) near6 semiconductor)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/06 12:02
L9	23	situ near2 method and ((detect\$3 or measur\$3) or monitor\$3) near15 ((particle or defect)) and compar\$3 near9 threshold	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/06 12:13
L10	0	situ and ((detect\$3 or measur\$3) near9 particles) and film near2 pell\$3 and react\$3 near2 chamber and compar\$3 near9 threshold	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/06 12:15

L11	0	situ and ((detect\$3 or measur\$3) near9 particles) and film near2 peel\$3 and react\$3 near2 chamber and compar\$3 near9 threshold	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/06 12:15
L12	19	situ and ((detect\$3 or measur\$3) near9 particles) and react\$3 near2 chamber and compar\$3 near9 threshold	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/06 12:16
L13	39	situ and (detect\$3 or measur\$3) near9 (particles near6 (wafer or substrate)) and compar\$3 near9 threshold	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/06 12:17
L14	17	13 and wavelength	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/06 12:21
L15	0	13 and predetermin\$3 near2 wavelength	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/06 12:18
L16	1	(predetermin\$2 near1 wavelength) near5 (particles near6 (wafer or substrate))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/06 12:22
L17	62	(predetermin\$2 near1 wavelength) near5 (particles)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/06 12:23
L18	71889	measur\$3 near6 intensity	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/06 12:23
L19	13	17 and 18	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/06 12:25
L20	43	compar\$ near9 (threshold near1 values) and (detect\$3 or measur\$3) near9 (particles near6 (wafer or semiconductor))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/06 12:26

L21	120	compar\$ near9 (threshold) and (detect\$3 or measur\$3) near9 (particles near6 (wafer or semiconductor))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/06 12:26
L22	18	21 and wavelength and period near time	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/06 12:27
L23	12	21 and wavelength and intensity near value	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/06 12:31
L24	1	yi-ling near chen	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/06 12:33
L25	472	react\$3 near chamber near condition	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/06 12:33
L26	37	chamber near condition and film near2 peel\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/06 12:34
L27	13	26 and particles	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/06 12:34